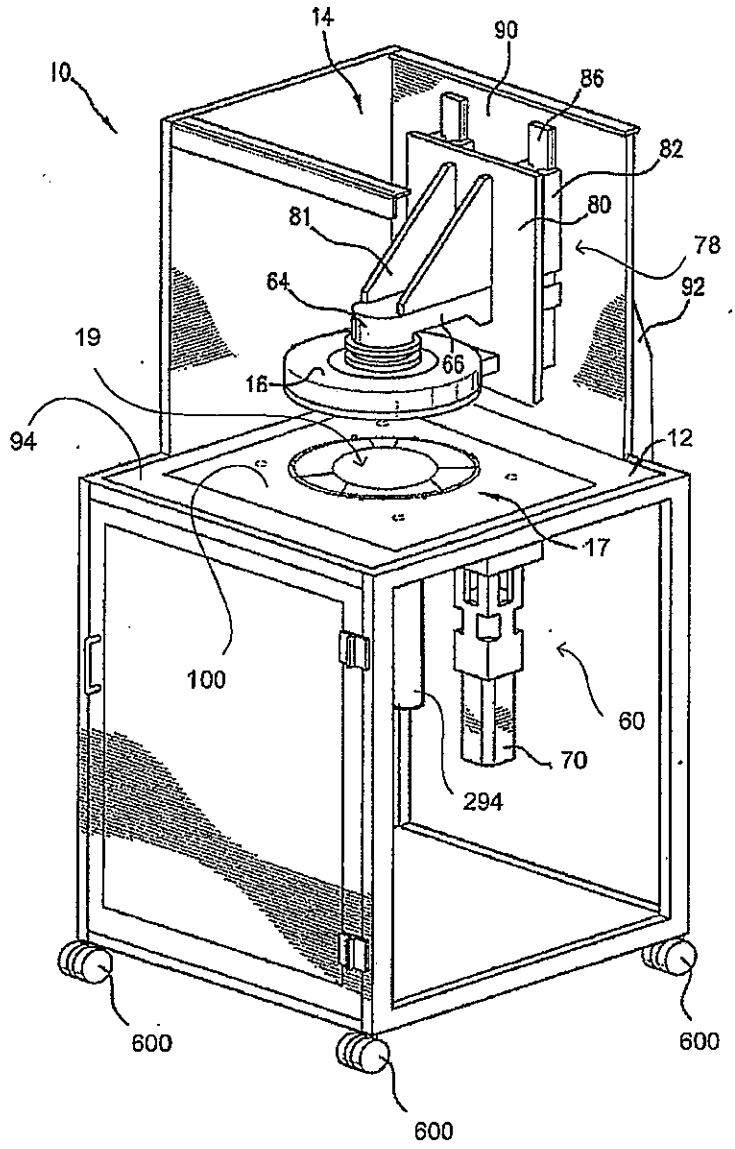

14
90
10
86
82
80
81
78
64
92
19
66
16
94
12
17
100
60
70
294
600
600
600

FIG. 1

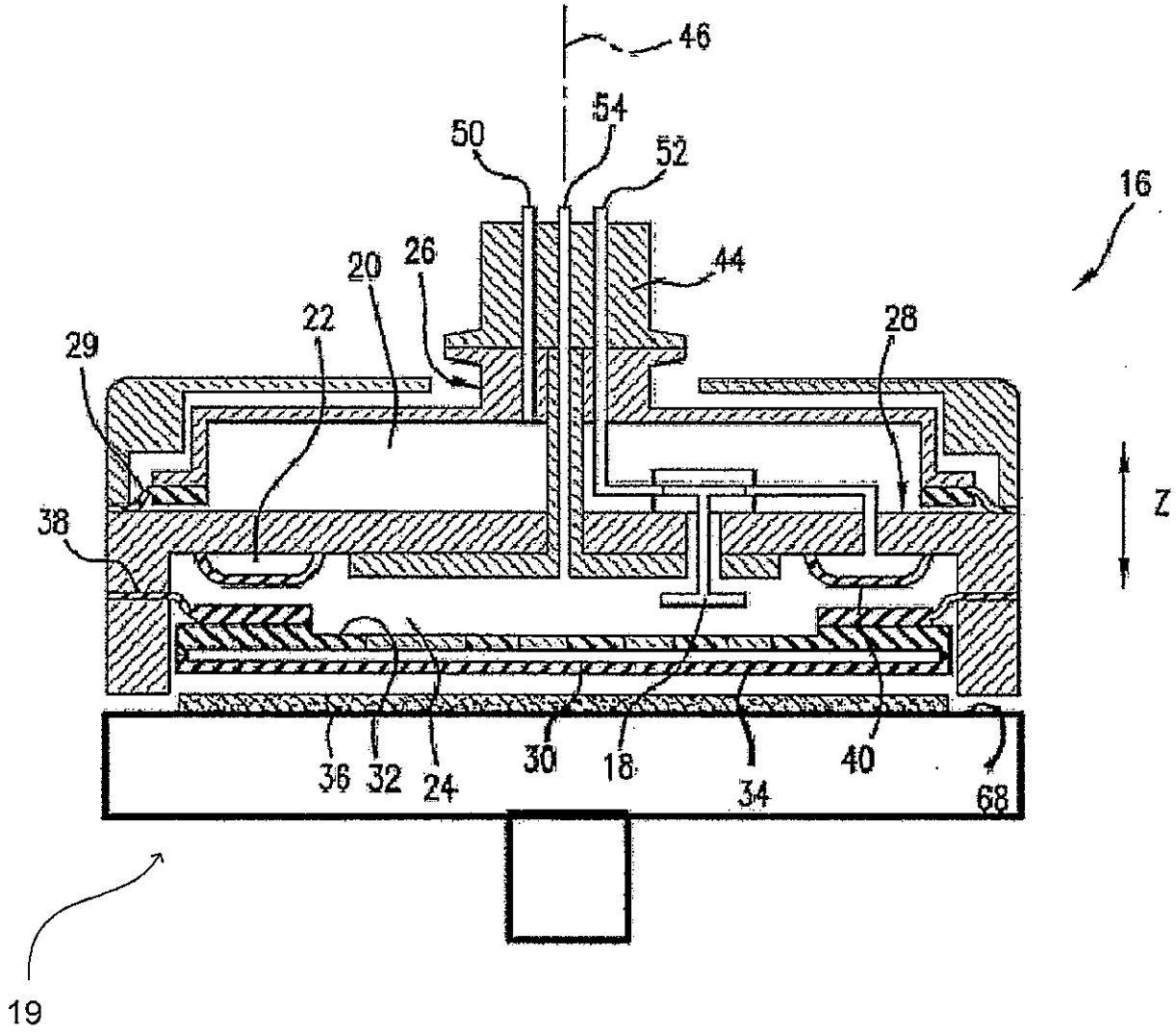


FIG. 2

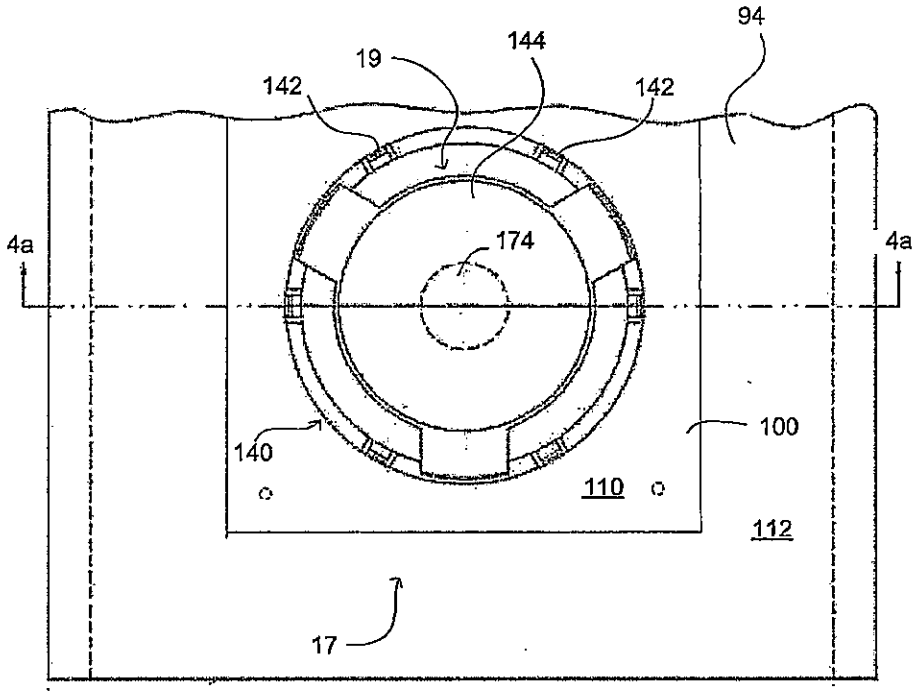

94
144
19
142
142
4a
174
4a
100
140
110
112
17

FIG. 3

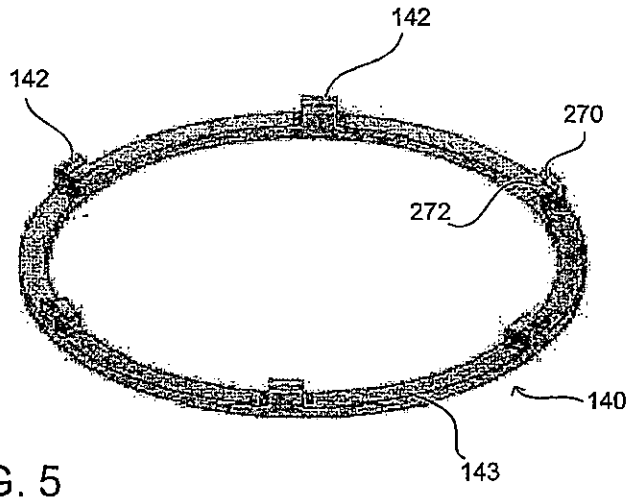

142
142
270
272
140
143

FIG. 5

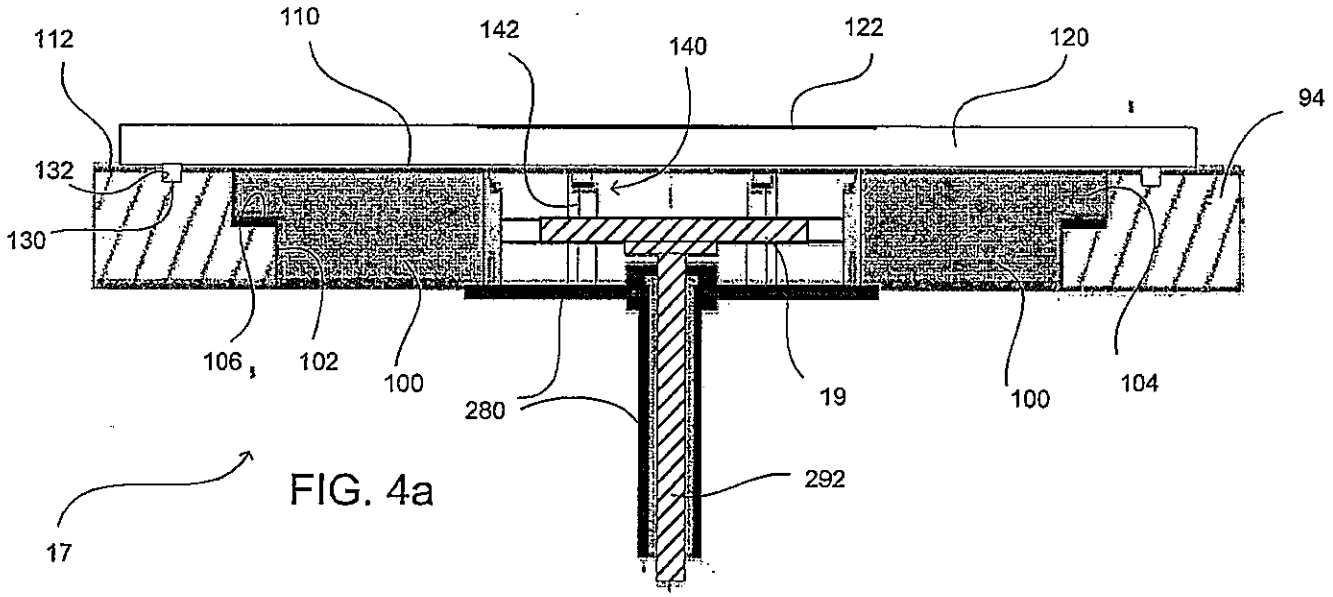

112
110
142
140
122
120
94
132
130
106
102
100
280
19
100
104
292
17

FIG. 4a

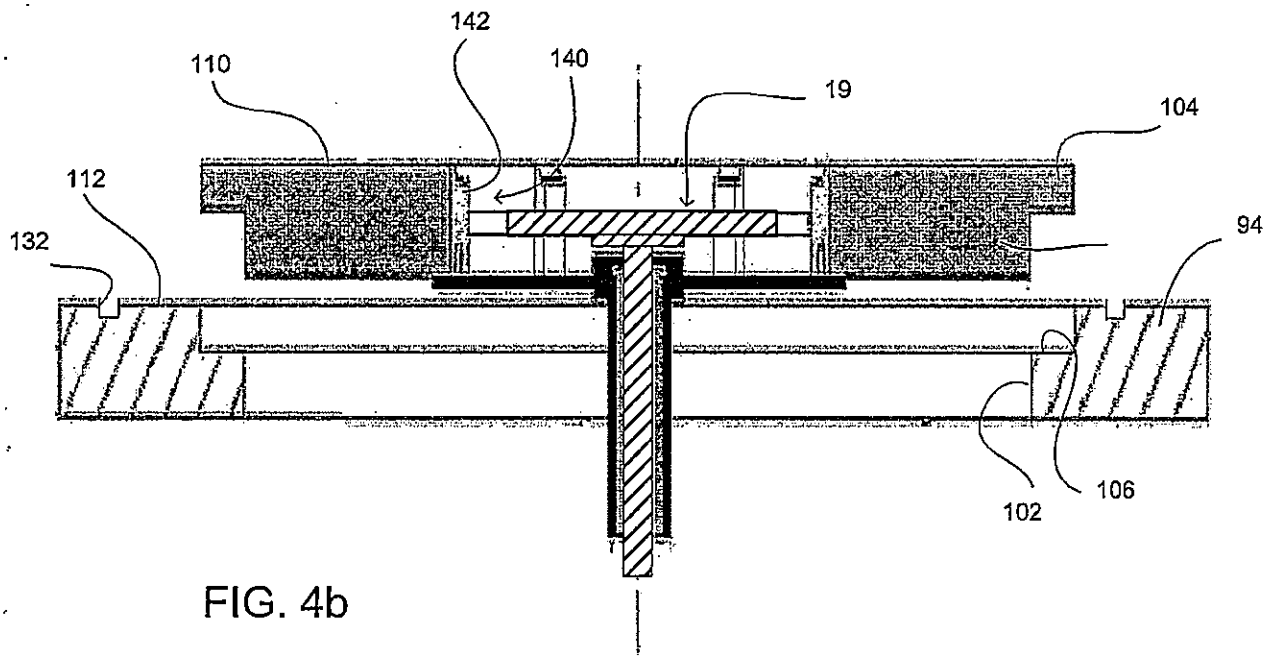

142
110
140
19
104
112
132
94
102
106

FIG. 4b

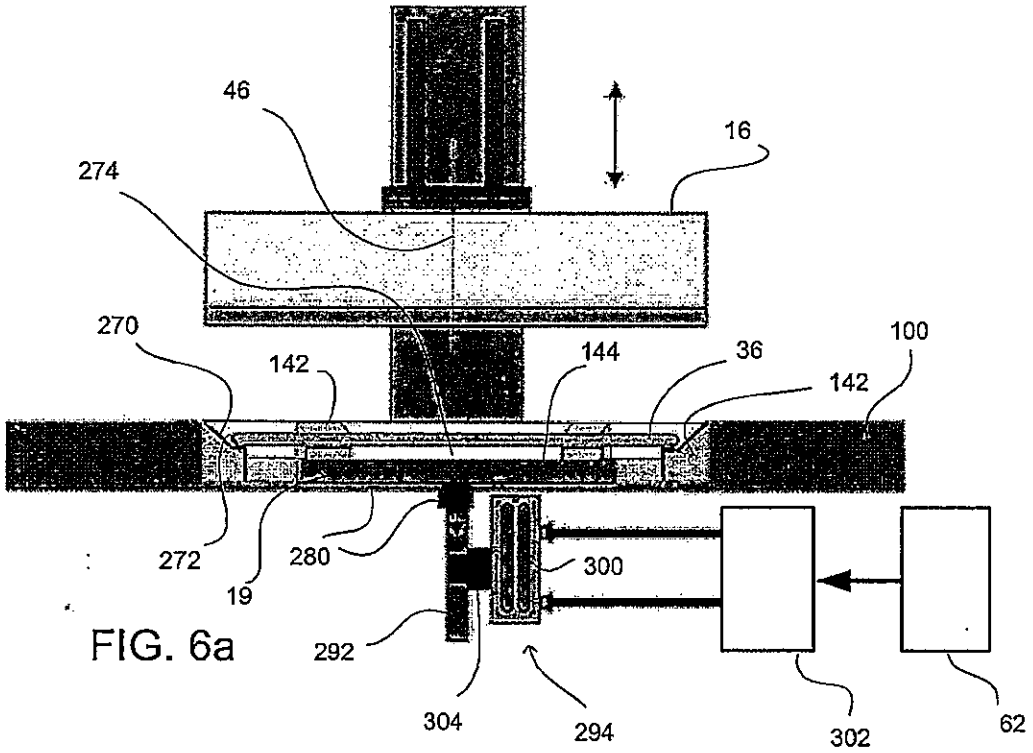

46
16
274
270
142
144
36
142
100
272
280
19
300
292
304
294
302
62

FIG. 6a

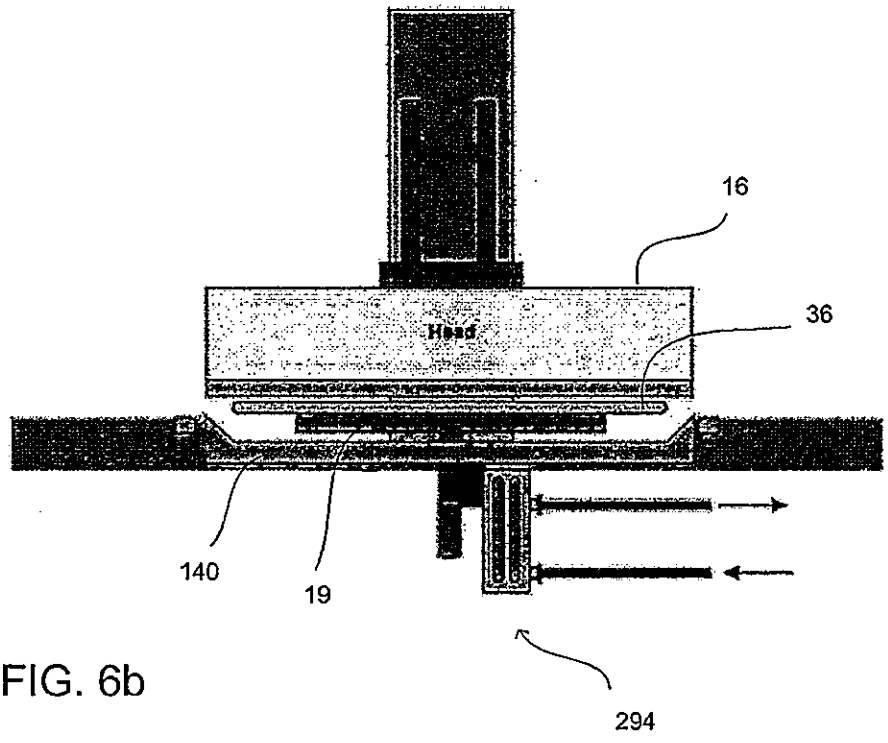

16
36
Head
140
19
294

FIG. 6b

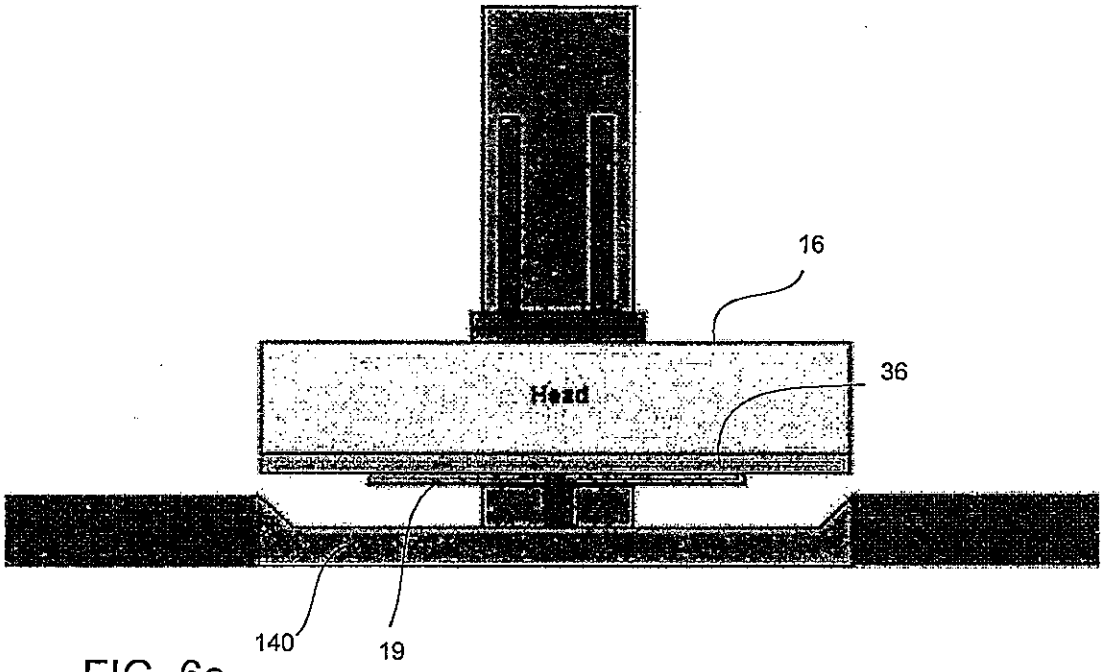


FIG. 6c

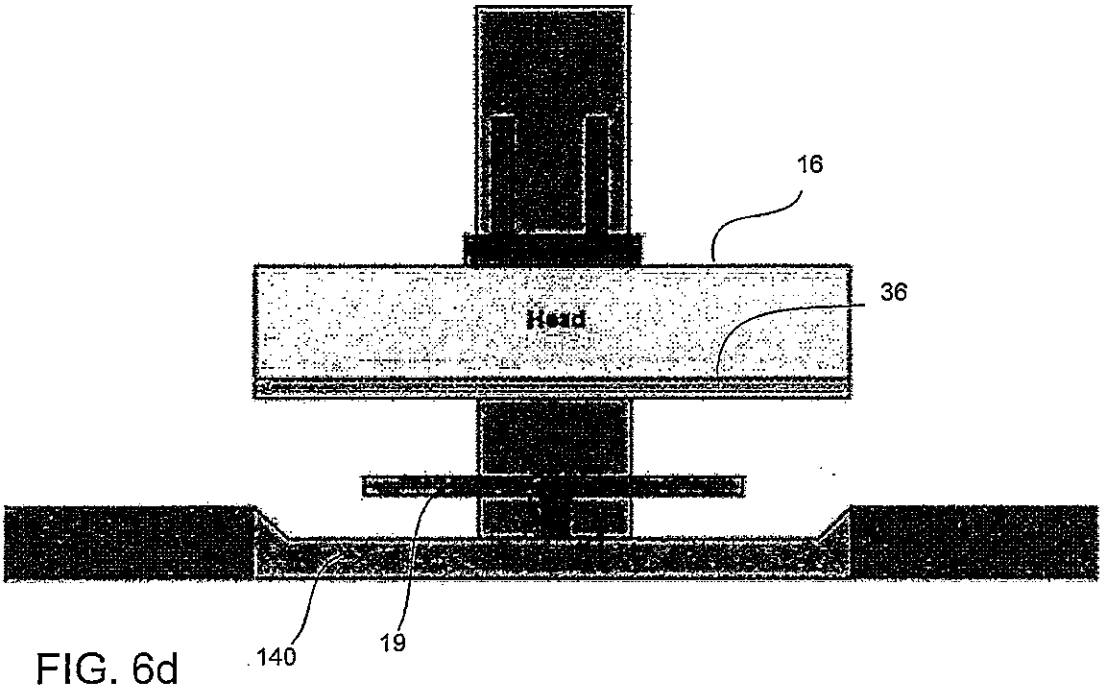


FIG. 6d

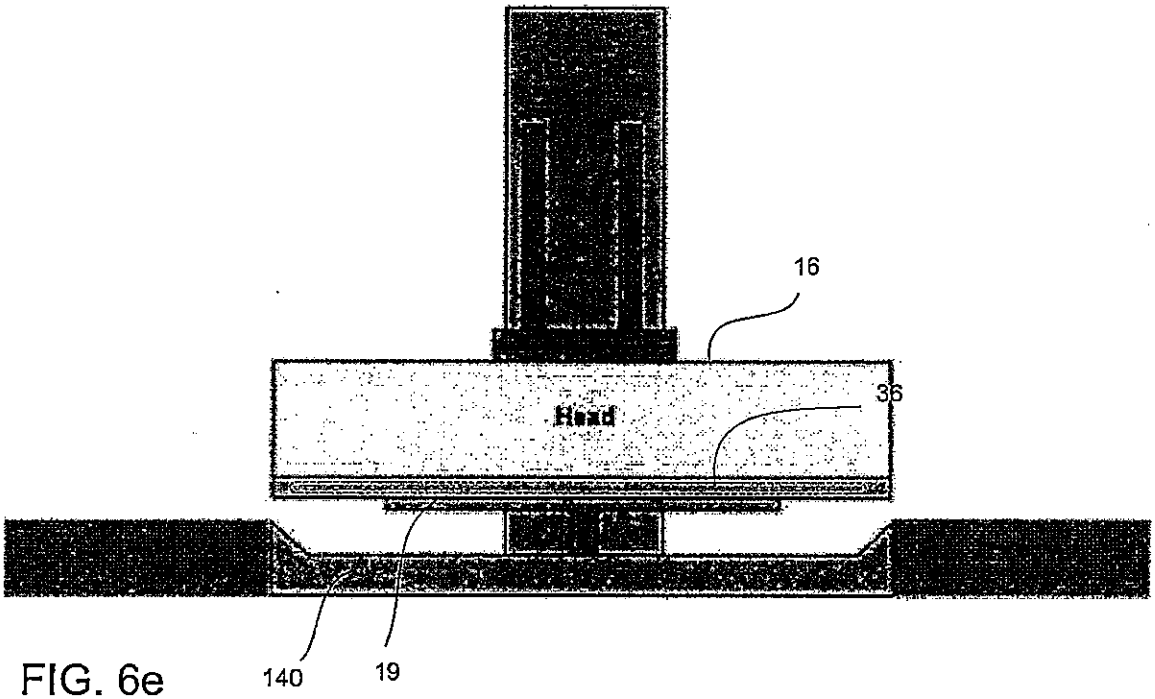


FIG. 6e

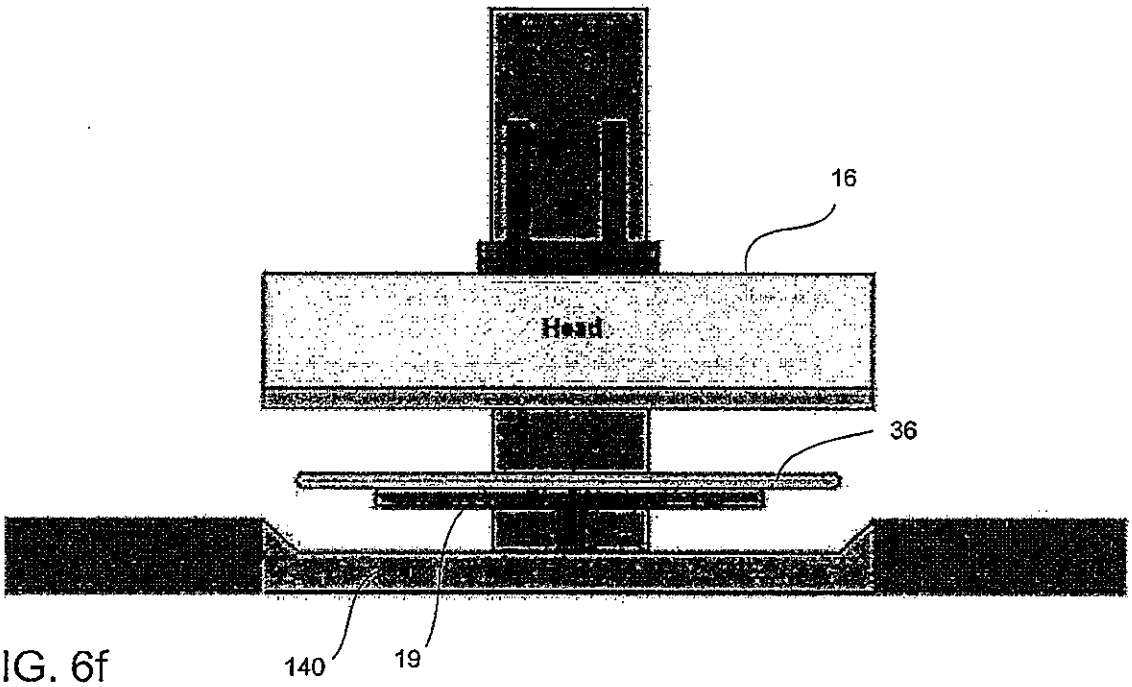


FIG. 6f

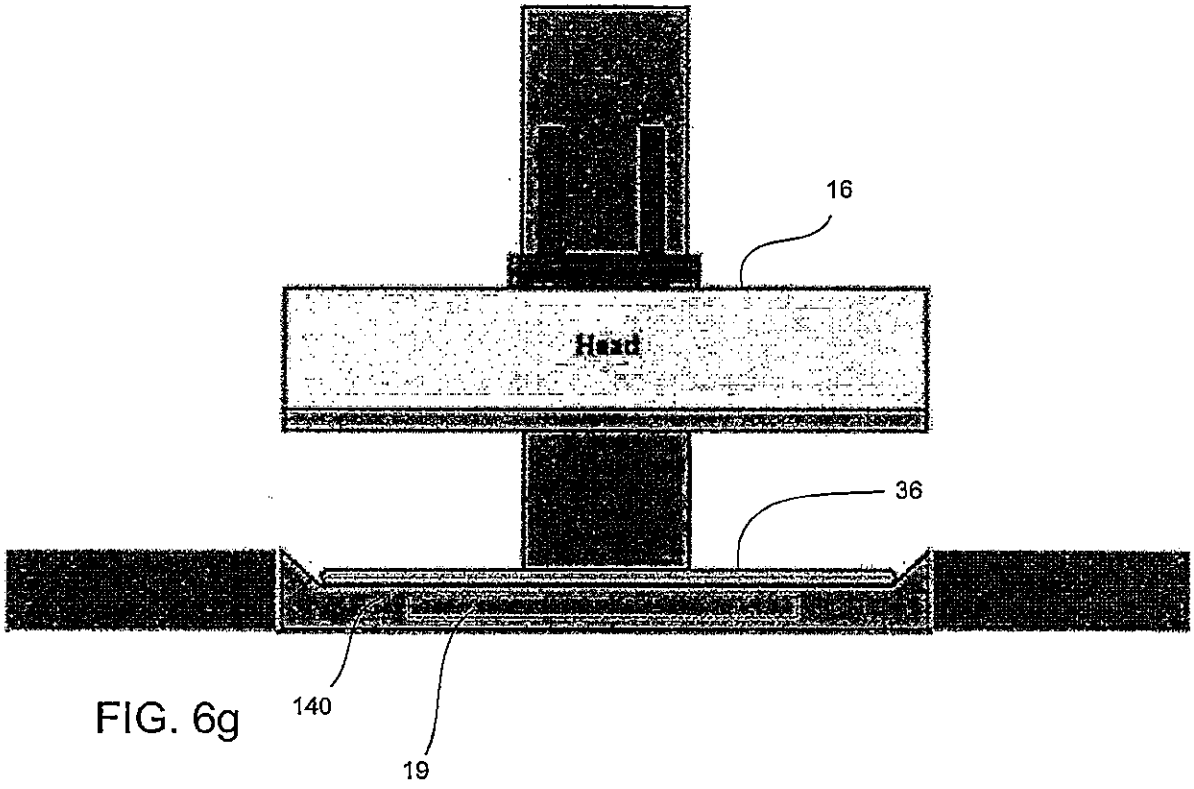


FIG. 6g

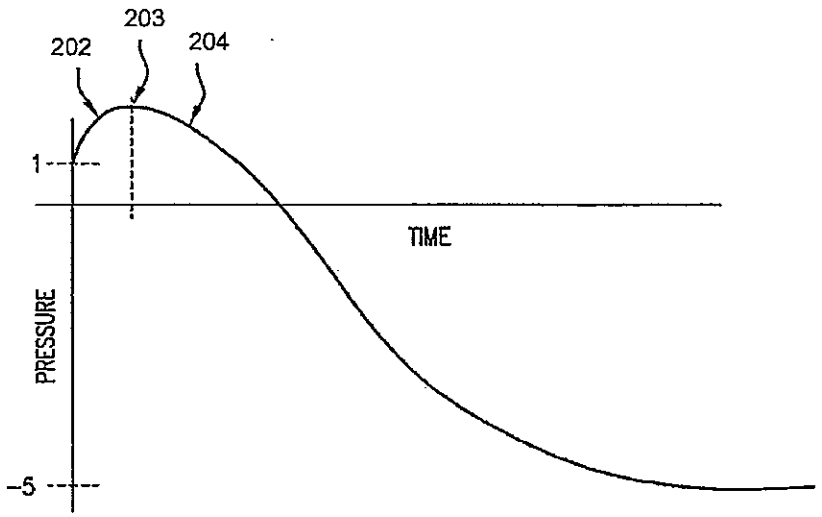


FIG. 8

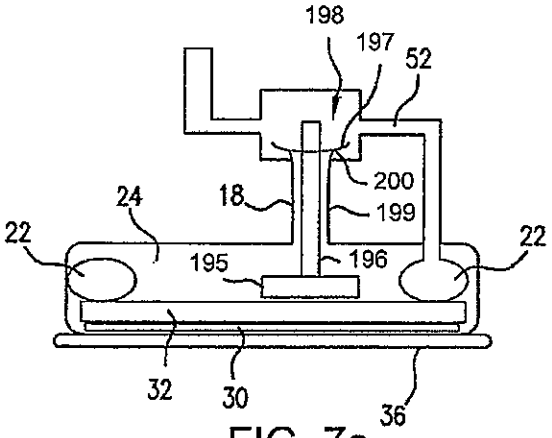

198
197
52
200
199
18
24
22
22
195
196
32
30
36

FIG. 7a

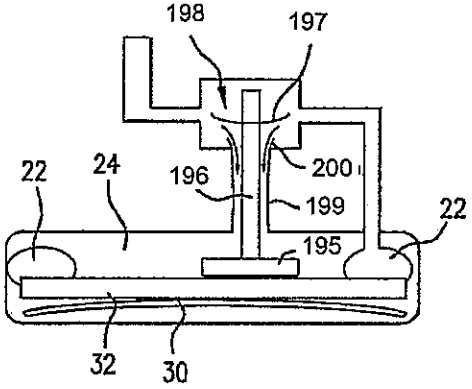

198
197
200
199
22
24
196
22
195
32
30

FIG. 7b

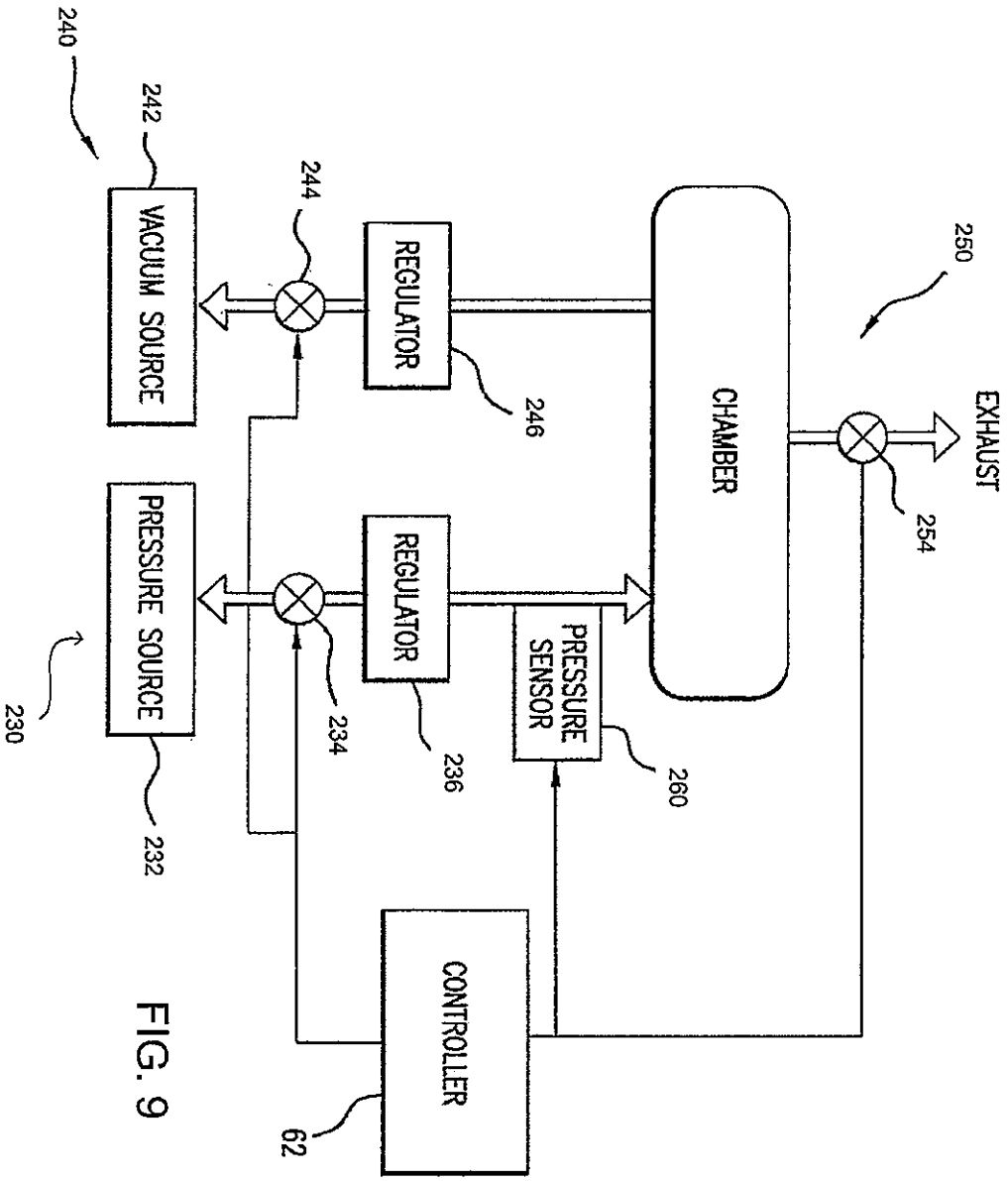

240
242
VACUUM SOURCE
244
REGULATOR
246
CHAMBER
250
EXHAUST
254
PRESSURE SOURCE
230
232
234
REGULATOR
236
PRESSURE SENSOR
260
CONTROLLER
62

FIG. 9

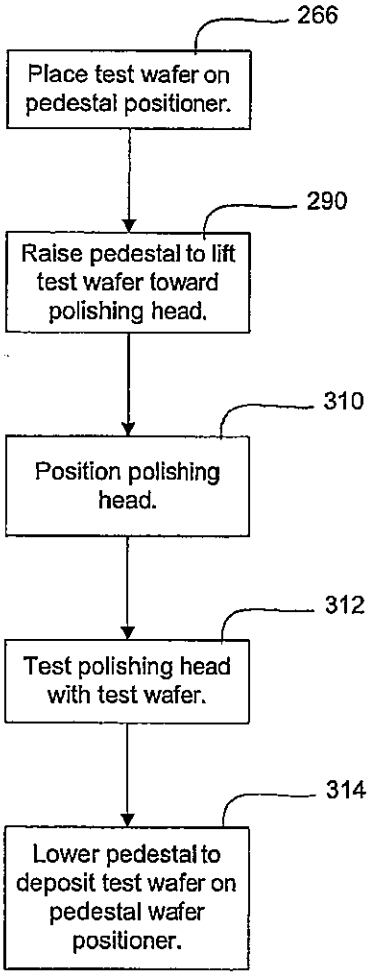

266
Place test wafer on pedestal positioner.
290
Raise pedestal to lift test wafer toward polishing head.
310
Position polishing head.
312
Test polishing head with test wafer.
314
Lower pedestal to deposit test wafer on pedestal wafer positioner.

FIG. 10

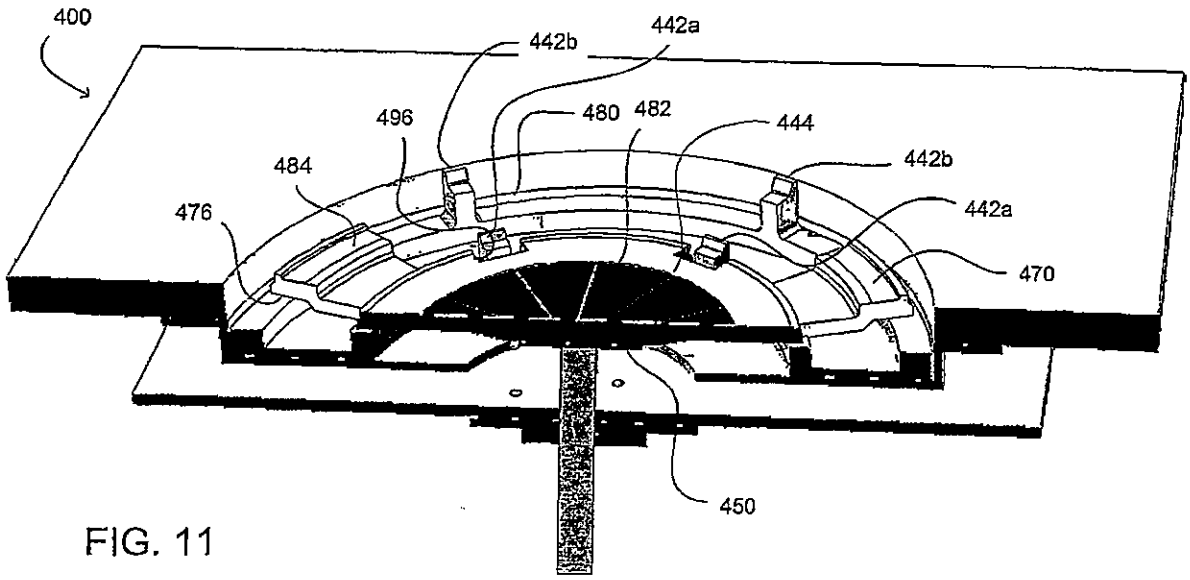

400
442b
442a
496
480
482
444
484
442b
476
442a
470
450

FIG. 11

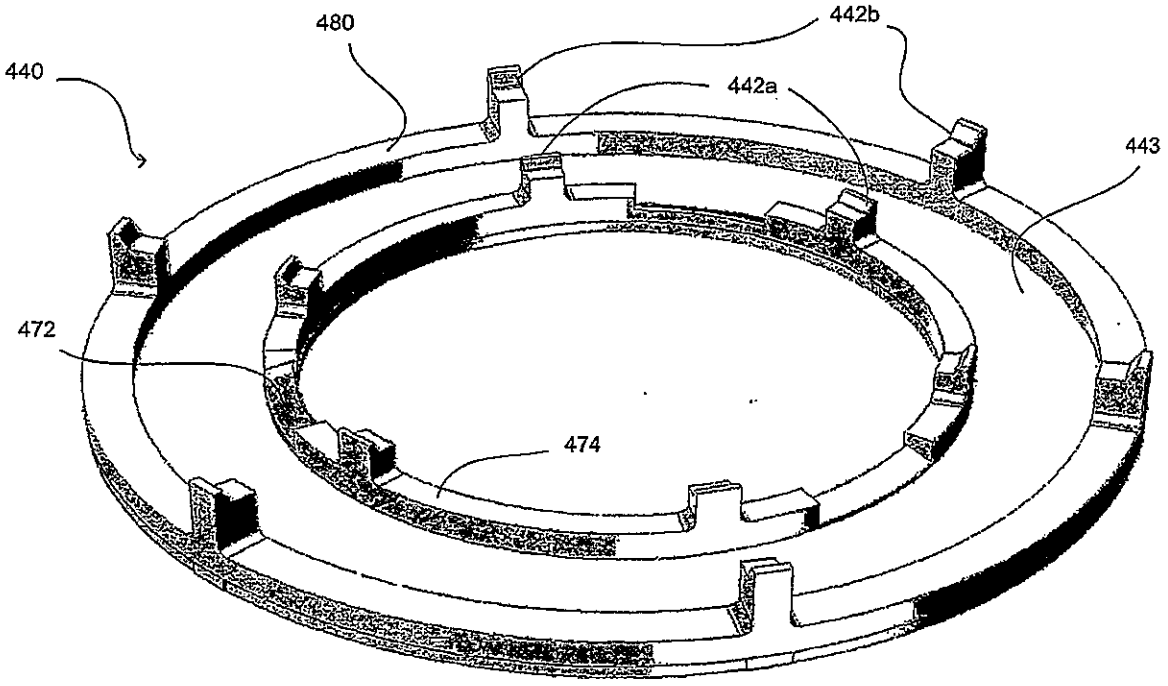

480
442b
440
442a
443
472
474

FIG. 12

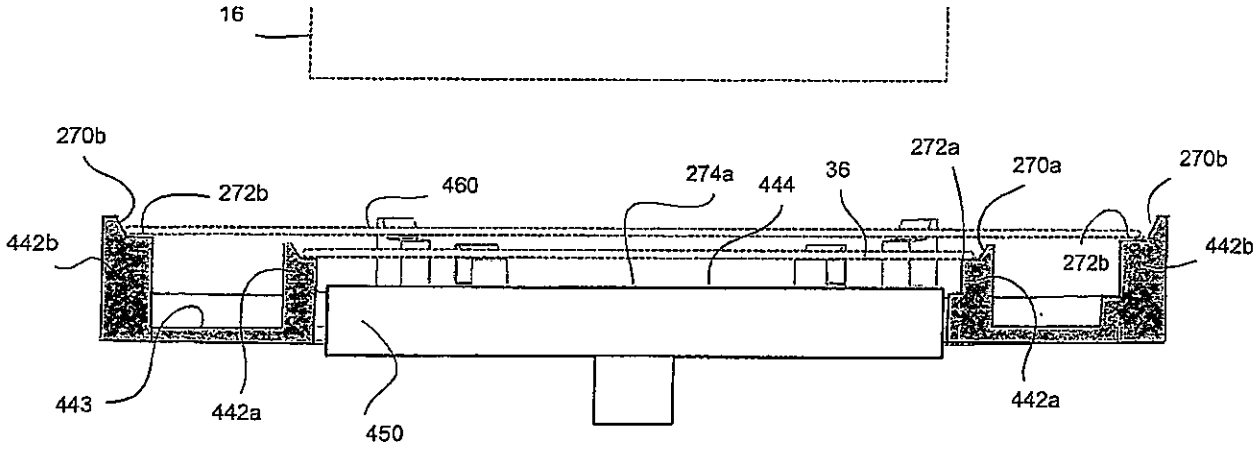

16
270b
272b
460
274a
444
36
272a
270a
270b
442b
272b
442b
443
442a
450
442a

FIG. 13

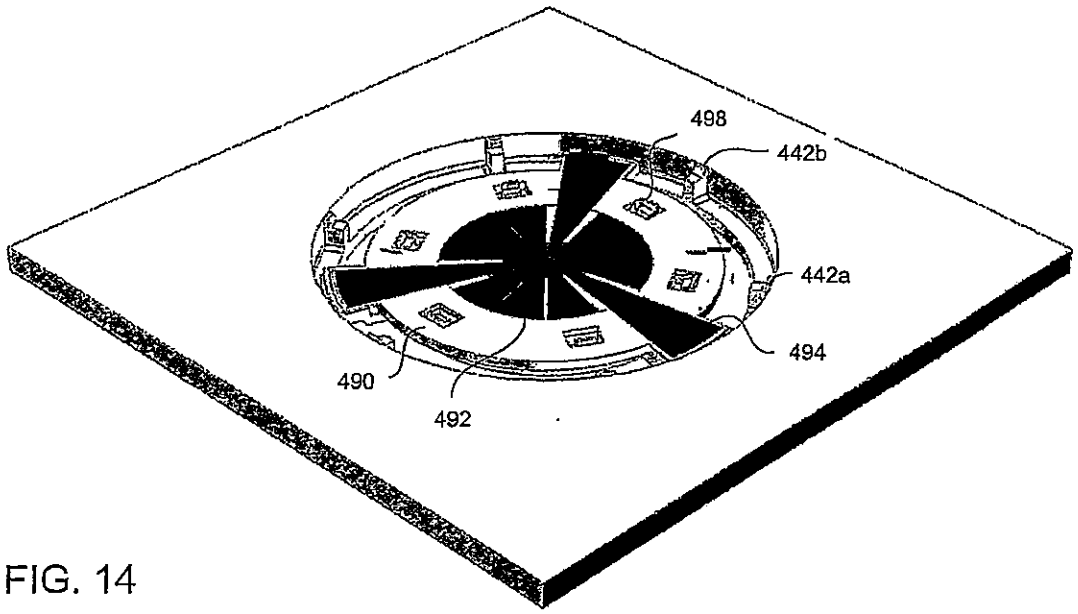

498
442b
442a
494
490
492

FIG. 14